

# Nitride-Based Heterojunction Bipolar Transistors (HBTs)

## Motivation

Group-III nitrides are expected to be applied to high power and high temperature operation electron devices due to their wide bandgap. However, predicted superior characteristics have never been achieved for nitride-based HBTs due to the low crystal quality or immature fabrication process. The purpose of this work is to investigate the excellent properties of group-III nitride semiconductors after solving these problems.

## Originality

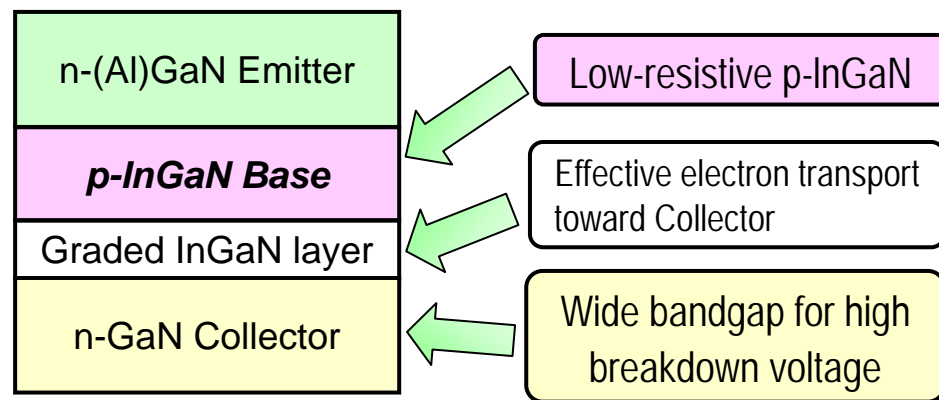
Using a low-resistive p-InGaN base and selective area regrowth technique, we have achieved high current gains of 3000 for nitride-based HBTs. They have also shown the 10-times higher breakdown electric field, which is comparable to the theoretically expected value. Furthermore, we have succeeded in high temperature operation of 300°C in Pnp HBTs. These results indicated that nitride-based HBTs have the potentials for high power or high temperature operation.

## Impact

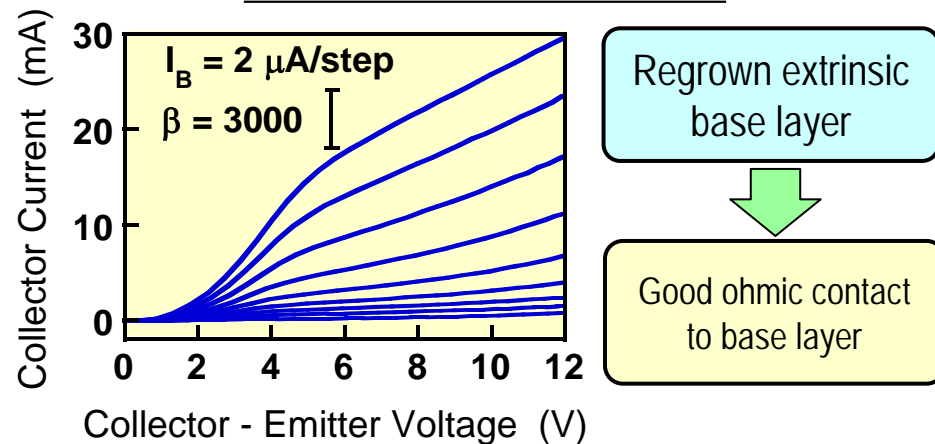
Nitride-based HBTs will be used for high power electron devices for communication between ground stations and satellites. They will reduce the system size drastically and increase the reliability, compared with vacuum tubes.

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## HBT structure



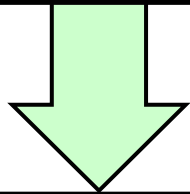
## Transistor characteristics



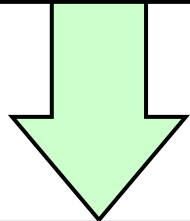
# *Feature of Nitride-based HBTs*

*Materials*

**Nitride semiconductors**



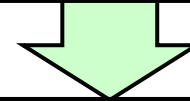
Wide bandgap



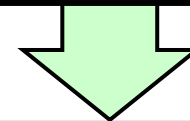
**Ultra-high power transistors**

*Electron devices*

**HBT**



High current density  
High breakdown field  
Uniform threshold voltage

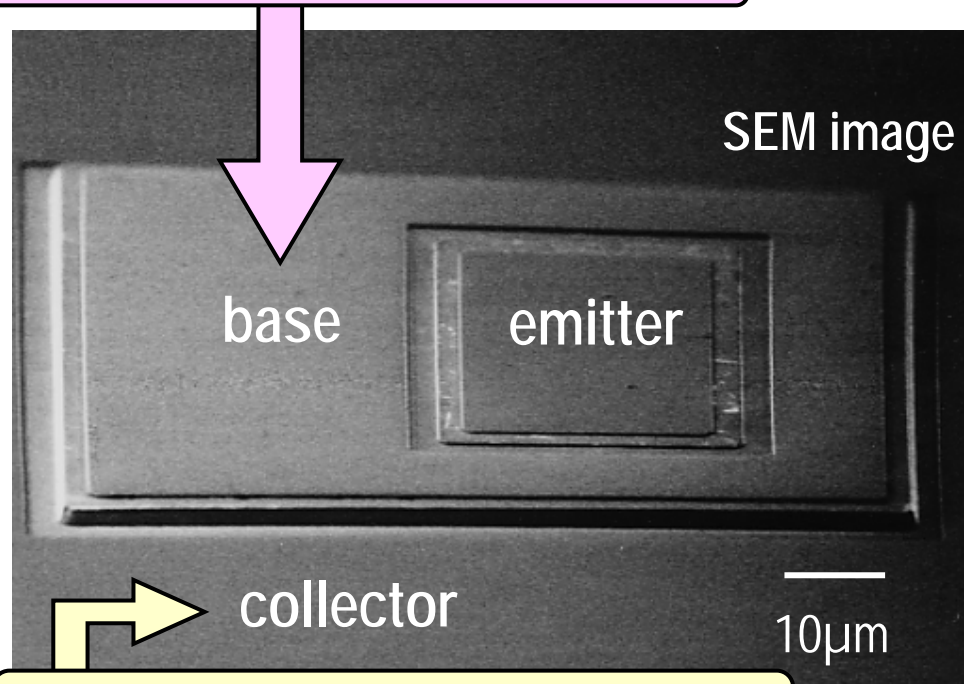


**Ultra-high power transistors**

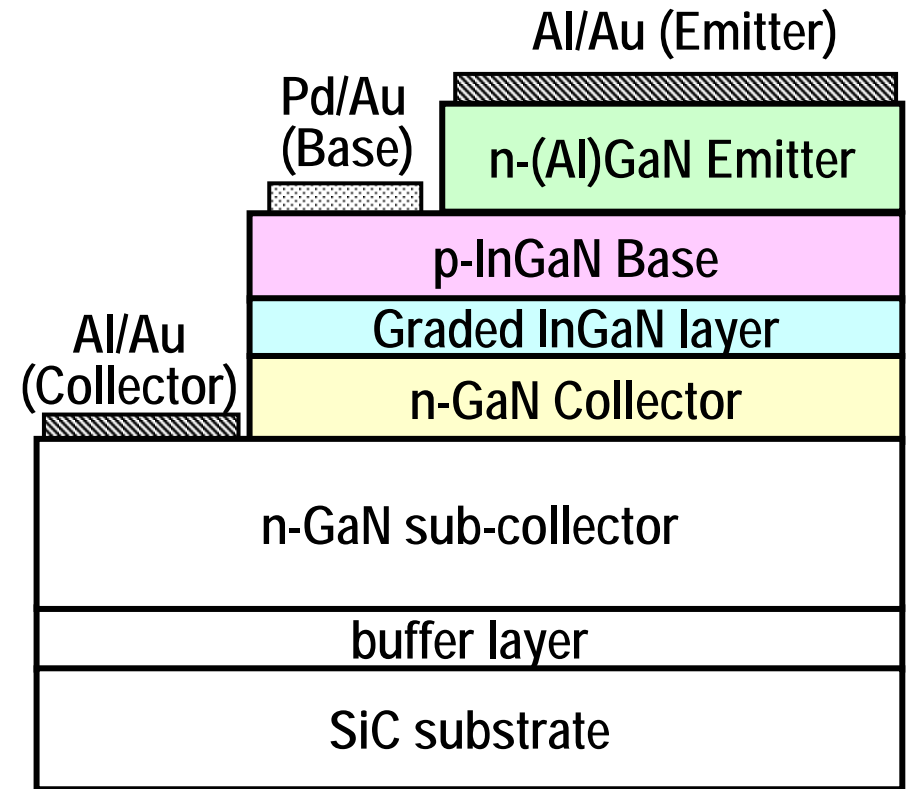


# Feature of our nitride HBTs

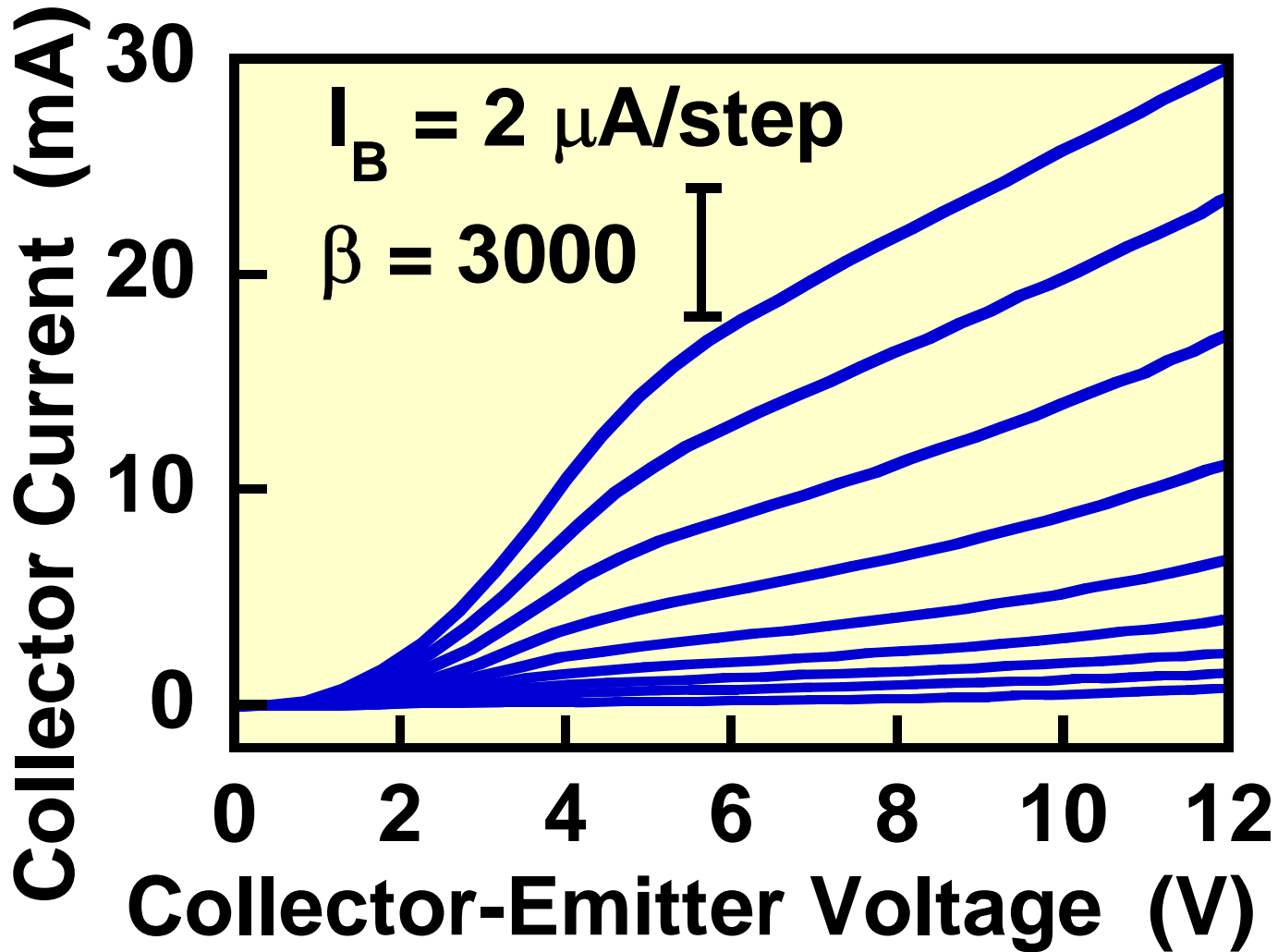
low-resistance p-InGaN



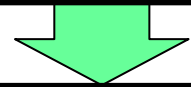
large breakdown voltage  
due to wide bandgap



# High current gain of Npn GaN/InGaN/GaN HBT



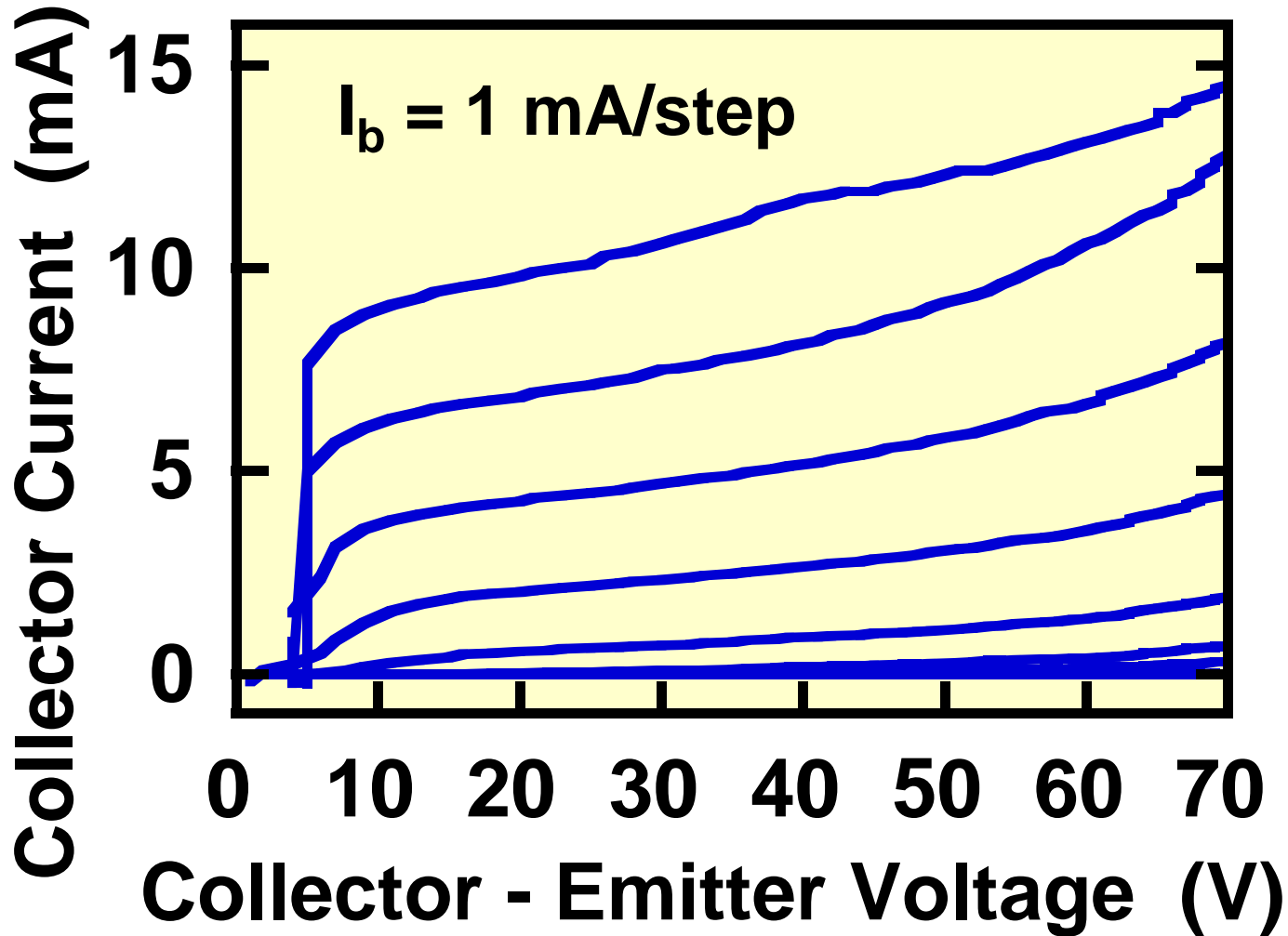
Current gain  
**3000 !**



Maximum value  
among nitride  
HBTs



# Large breakdown voltage of Npn AlGaIn/InGaIn/GaN HBT



Operation  
above 70 (V)

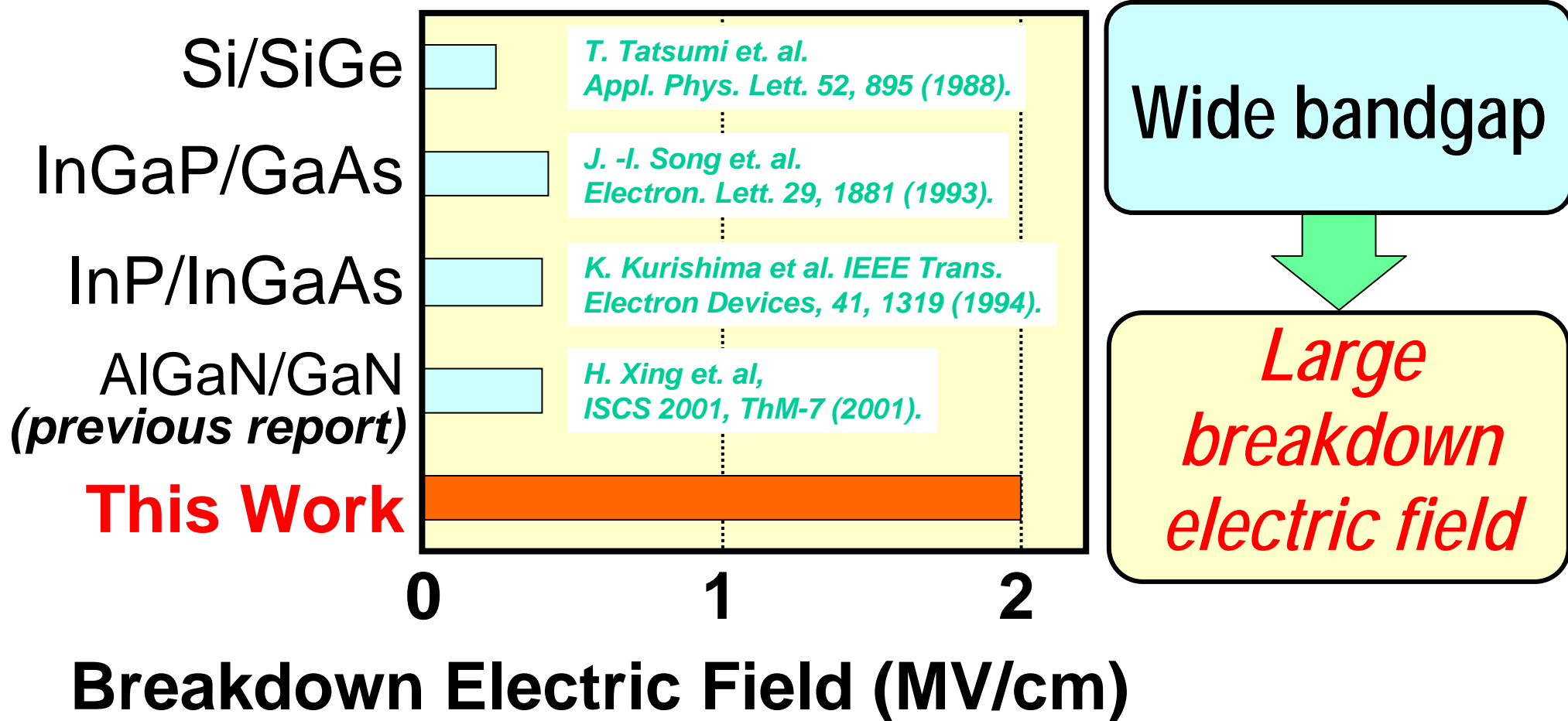
Breakdown  
electric field =  
2 (MV/cm)

High power  
application

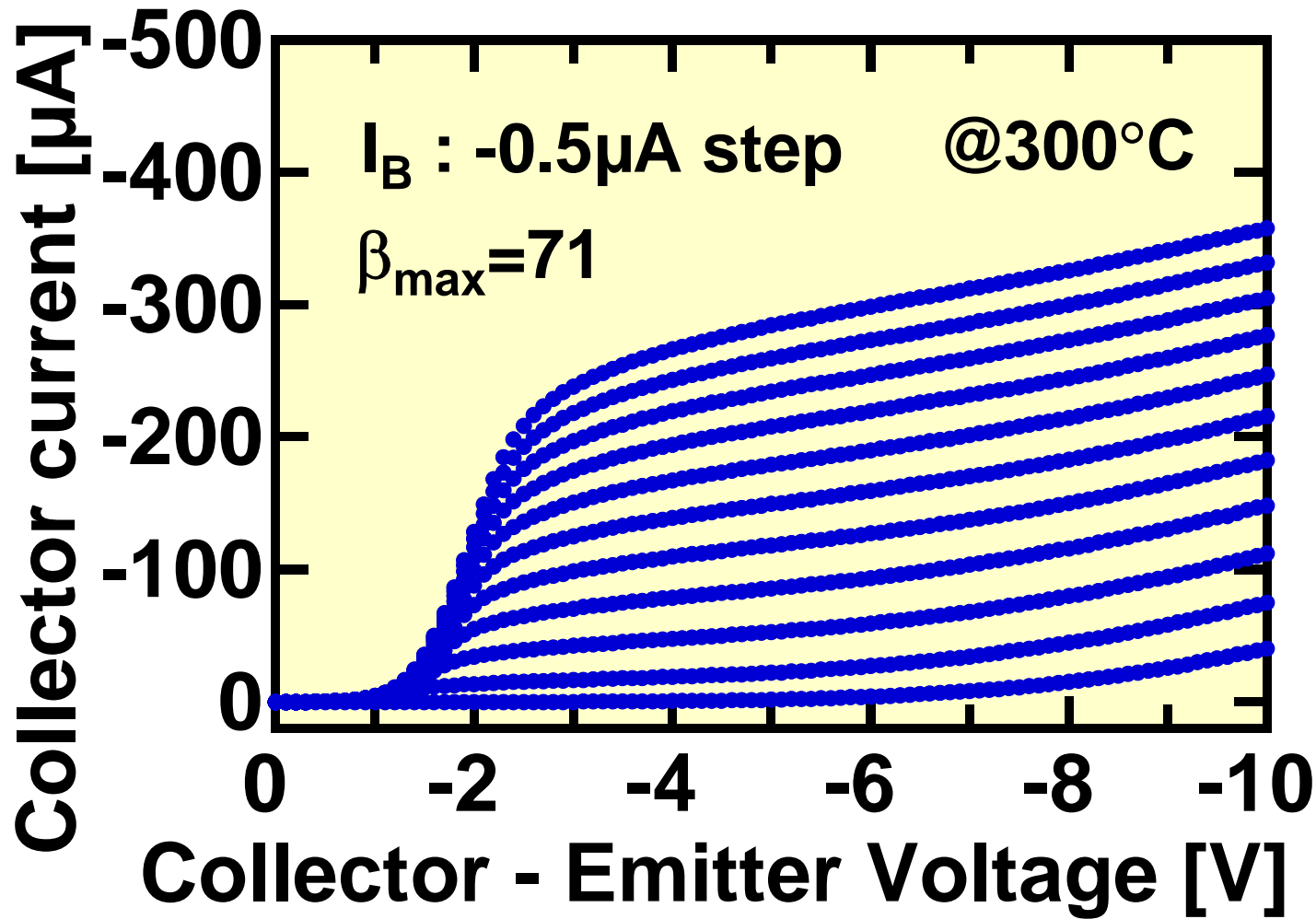


# Comparison of breakdown voltage in various HBTs

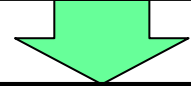
## HBT Materials



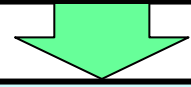
# High temperature operation of Pnp AlGaIn/GaN HBT



Ohmic device



Operation  
at  $300\ (^{\circ}\text{C})$



*Applicable in  
various  
circumstances*

